



# Registration open for: DWL Workshop and Webinar Series

Join us for the 3rd DWL Workshop on Wednesday 19th February at RMIT, Melbourne proudly sponsored by ANFF. This one-day event is designed for researchers, scientists, and micro and nanofabrication experts to explore the latest advancements in Direct Write Lithography (DWL) and push the boundaries of micro and nanoscale fabrication. Don't miss this opportunity to connect with industry leaders!"

Additionally, attendees will benefit from a series of 5 educational webinars beginning in October 2024. These webinars will deepen your understanding of lithography resists, from the basics to more complex uses.

## Want to present at the workshop?

We're calling on researchers, scientists, and experts in micro and nanofabrication to share their insights at the "Innovative Research in Direct Write Lithography Workshop." If you're working on new techniques, applications, or advancements in direct write lithography, we want to hear from you. For details on how to submit your abstract, scan the QR code on the right or [click here](#).



	Melb, Syd	Adelaide	Perth	Berlin	NY	LA	Topic / Title	Facilitator / Speaker
W1	AEDT 11:00 23.10.24	ACDT 10:30 23.10.24	AWST 08:00 23.10.24	CEST 02:00 23.10.24	EDT 20:00 22.10.24	PDT 17:00 22.10.24	The History of Lithography Resists	Christopher K Ober* (Cornell University)
W2	AEDT 16:00 20.11.24	ACDT 15:30 20.11.24	AWST 13:00 20.11.24	CET 06:00 20.11.24	EST 00:00 20.11.24	PST 21:00 19.11.24	Basics of Micro Structuring – Photolithography with the AZ and MC range of photoresists	Titus Rinke (Microchemicals)
W3	AEDT 14:00 11.12.24	ACDT 13:30 11.12.24	AWST 11:00 11.12.24	CET 04:00 11.12.24	EST 22:00 10.12.24	PST 19:00 10.12.24	The Physics of Lithography Resists	Scott Lewis (Caltech)
W4	AEDT 17:00 22.01.25	ACDT 16:30 22.01.25	AWST 14:00 22.01.25	CET 07:00 22.01.25	EST 01:00 22.01.25	PST 22:00 21.01.25	Chemical fundamentals and innovations in MRT's photoresist portfolio	Anja Voigt, Christine Schuster, Arne Schleunitz (micro resist technology)
W5	AEDT 11:00 12.02.25	ACDT 10:30 12.02.25	AWST 8:00 12.02.25	CET 01:00 12.02.25	EST 19:00 11.02.25	PST 16:00 11.02.25	EBL resists and their exposure mechanisms: from PMMA to Hydrogels	Leonidas E Ocola (IBM T.J. Watson Research Centre)
W6	AEDT 14:00 05.03.25	ACDT 13:30 05.03.25	AWST 11:00 05.03.25	CET 04:00 05.03.25	EST 22:00 04.03.25	PST 19:00 04.03.25	What are the challenges for creating a next generation resist?	Scott Lewis (Caltech)

\* Please be aware that the webinar you'll be watching is a pre-recorded session. After the presentation, there will be a live Q&A segment with Christopher Ober.

SCAN TO REGISTER FOR THE EVENT OR [CLICK HERE](#)



+ CONTACT

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